

App. No. 10/761,081  
Office Action Dated May 4, 2005

### REMARKS

Favorable reconsideration of this application is requested in view of the above amendments and the following remarks. Claim 9 is hereby amended. No new matter has been added. Claims 9-12 are pending.

The amendment of claim 9, reciting "after forming the pad layer", is supported by Figures 2-5 and page 10, lines 15-23.

Claims 9-12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kwon et al. (US 2002/0022301) in view of Chen et al. (US 2003/0013291). Applicant respectfully traverses this rejection.

Kwon et al. does not disclose patterning the intermediate layer and the pad layer after forming the pad layer, as required by claim 9. Rather, the disclosure of Kwon et al. is directed to provide layers of under barrier metal and metal bump formed via the opening portion of a passivation layer on the chip pad. Paragraphs [0023-24]. Applicant respectfully directs the Examiner to Figs. 6-7, which show the process of formation of the layers on the electrode pad and the resultant structure are very different from that of the current invention. For at least these reasons, claim 9 and claims 10-12, which depend therefrom are distinguishable from Kwon et al.

The rejection further relies on the teaching of Chen et al. (US 2003/0013291) for the teaching of benzocyclobutene as a material for a passivation layer. Applicant respectfully traverses this rejection. Even if Chen et al. alleges that benzocyclobutene has been used as a passivation material, the cited reference teaches away from using the organic polymer as a final passivation layer. The final passivation layer taught by Chen et al. consists of multiple layers of silicon dioxides and silicon nitride. Such materials are preferred by Chen et al. because they are allegedly easier to handle in the etching and metal deposition processes. Para. [0074] and Fig. 3. For at least these reasons, claim 9 and claims 10-12, which depend therefrom, are allowable over Kwon et al, and Chen et al. taken together or separately.

Favorable reconsideration of claims 9-12 is requested.

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In view of the above, favorable reconsideration in the form of a notice of allowance is requested. Any questions regarding this communication can be directed to the undersigned attorney, Douglas P. Mueller, Reg. No. 30,300, at (612)455-3804.

Respectfully Submitted,

Dated: August 30, 2005



DPM:unt

A handwritten signature in black ink, appearing to be "D. Mueller", written over a horizontal line.

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